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As *Industrial Chemistry & Materials* has grown as an international communication platform for cutting-edge research, we are deeply grateful for the strong support of our global scholarly community. The steady advancement of the journal reflects the combined efforts of authors, the editorial team, and most crucial, our dedicated reviewers, whose rigorous and insightful assessments underpin the scientific excellence and integrity that define our journal.

Supported by the committed reviewer community, *Industrial Chemistry & Materials* has further strengthened its academic quality and expanded its global reputation. *Industrial Chemistry & Materials* has been indexed in ESCI, EI Compindex, Scopus, IET INSPEC, and DOAJ. In 2025, the journal received its first Impact Factor of 11.9, ranking 10/175 in *Engineering, Chemical* and 45/460 in *Materials Science, Multidisciplinary*, positioning it within JCR Q1. During the year, reviewers from 39 countries and regions generously contributed their time and expertise to *Industrial Chemistry & Materials*, collectively supporting the journal in advancing the internationalization, fairness, and transparency of the peer-review process. In recognition of their exceptional efforts, our editorial team has carefully selected a group of reviewers who have made significant contributions and gone above and beyond in providing timely, rigorous, and constructive feedback. It is our pleasure to recognize these contributors as our Outstanding Reviewers for 2025:

Outstanding Reviewers for *Industrial Chemistry & Materials* in 2025

We would like to take this opportunity to thank all of *Industrial Chemistry & Materials*'s reviewers for helping to preserve quality and integrity in chemical science literature. We would also like to highlight the Outstanding Reviewers for *Industrial Chemistry & Materials* in 2025.

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As we recognize our Outstanding Reviewers for 2025, we also extend our sincere appreciation to the broader *Industrial Chemistry & Materials* community—our Editorial and Advisory Boards, authors, reviewers, and readers—whose collective efforts sustain the journal's progress. Looking ahead, we remain firmly committed to upholding a peer review system grounded in fairness, rigor, and transparency, while continuing to broaden its global reach. Together, we will advance a culture of trust, integrity, and excellence that underpins high-quality scientific publishing.

Suojiang Zhang, Editor-in-Chief
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